

AMAT Docket No. 2616 US/RTP/LE
BSTZ Docket No. 4887P090

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:

Guangcai Xing, et al.

Application No. 09/298,064

Filed: April 22, 1999

For: APPARATUS AND METHOD FOR EXPOSING
A SUBSTRATE TO PLASMA RADICALS

Examiner: Zervigon, R.

Art Unit: 1763

Box Fee Amendment
Assistant Commissioner for Patents
Washington, D.C. 20231

RESPONSE TO OFFICE ACTION

In response to the Office Action dated April 17, 2002, Applicants respectfully request entry of the amendments set forth below and consideration of the remarks that follow.

IN THE CLAIMS

Please substitute the following amended claims for the pending claims with the same numbers:

- 1 17. (Four Times Amended) A system for reacting a plasma with a substrate,
- 2 comprising:
- 3 a first chamber;
- 4 a nitrogen gas source coupled to the first chamber comprising constituents adapted to react
- 5 with a substrate;
- 6 an energy source coupled to the first chamber;
- 7 a second chamber configured to house a substrate for film formation processing;
- 8 a system controller configured to control the introduction of a gas from the gas source into
- 9 the first chamber and to control the introduction of an energy from the energy source; and